

ABSTRACT OF THE DISCLOSURE

A semiconductor cleaning device having a substantially cylindrical roller body made of polyvinyl acetal with a smooth outer surface and uniform material porosity having a mean flow pore pressure ranging from about 0.30 PSI to about 0.35 PSI with 95% of its pores ranging from 7 to 40 microns in size and a wet flow rate ranging from about 80.0 L/min to about 7.0 L/min.